### EE 330 Lecture 16

### **Devices in Semiconductor Processes**

- Diodes (continued)
- Capacitors
- MOSFETs

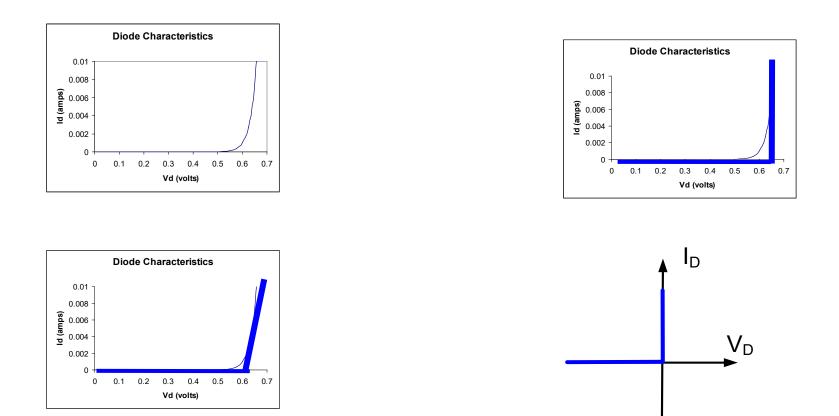
### Spring 2024 Exam Schedule

- Exam 1 Friday Feb 16
- Exam 2 Friday March 8
- Exam 3 Friday April 19

Final Exam Tuesday May 7 7:30 AM - 9:30 AM

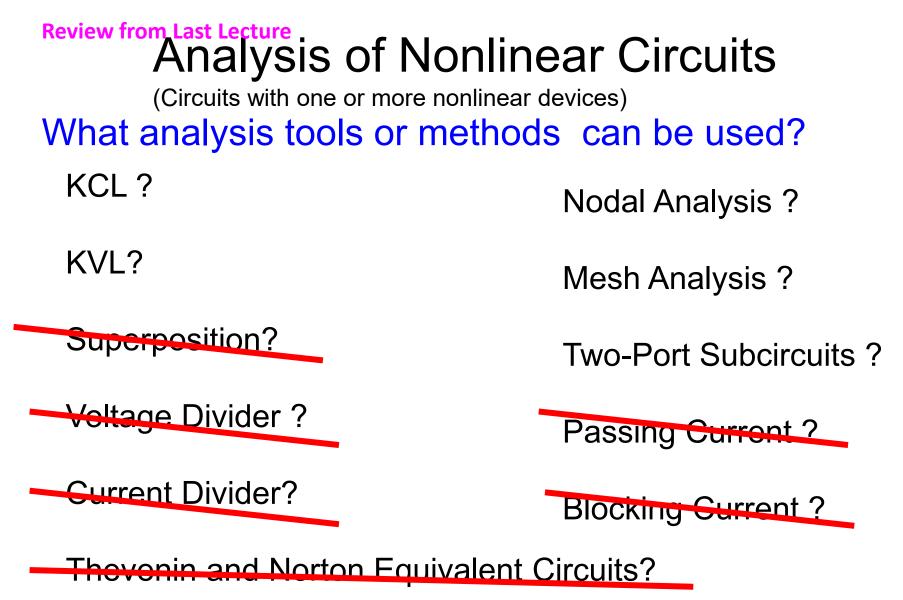
#### **Review from Last Lecture**

### **Diode Models**



#### Which model should be used?

The simplest model that will give acceptable results in the analysis of a circuit



- How are piecewise models accommodated?
- Will address the issue of how to rigorously analyze nonlinear circuits with piecewise models later

### Use of <u>Piecewise</u> Models for Nonlinear Devices when Analyzing Electronic Circuits

Process:

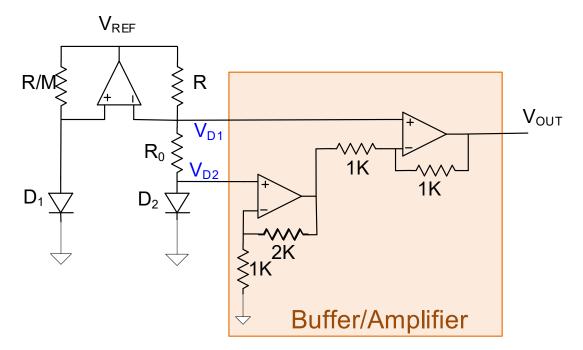
- 1. Guess state of the device
- 2. Analyze circuit
- 3. Verify State
- 4. Repeat steps 1 to 3 if verification fails
- 5. Verify model (if necessary)

#### **Observations:**

- o Analysis generally simplified dramatically (particularly if piecewise model is linear)
- Approach applicable to wide variety of nonlinear devices
- $\circ~$  Closed-form solutions give insight into performance of circuit
- $\circ~$  Usually much faster than solving the nonlinear circuit directly
- Wrong guesses in the state of the device do not compromise solution (verification will fail)
- $\circ$  Helps to guess right the first time
- Detailed model is often not necessary with most nonlinear devices
- o Particularly useful if piecewise model is PWL (but not necessary)
- For <u>practical</u> circuits, the simplified approach usually applies

#### Key Concept For Analyzing Circuits with Nonlinear Devices

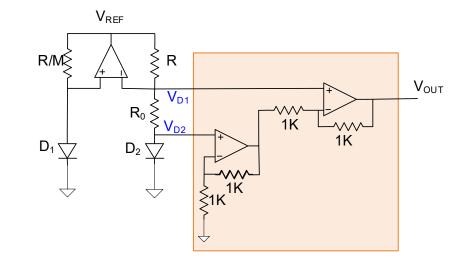
# A Diode Application



If buffer/amplifier added, serves as temperature sensor at  $V_{OUT}$  $V_{OUT} = 2(V_{D1} - V_{D2})$ May need compensation and startup circuits

For appropriate R<sub>0</sub>, serves as bandgap voltage reference (buffer/amplifier excluded)  $V_{REF} = V_{D1} + \frac{R}{R_0} (V_{D1} - V_{D2})$ 

# A Diode Application



$$V_{OUT} = 2 \left( V_{D1} - V_{D2} \right)$$

Analysis of temperature sensor (assume  $D_1$  and  $D_2$  matched)

$$I_{D2}(T) = \left(J_{SX}\left[T^{m}e^{\frac{-V_{os}}{V_{t}}}\right]\right)Ae^{\frac{V_{os}}{V_{t}}}$$

$$I_{D1}(T) = \left(J_{SX}\left[T^{m}e^{\frac{-V_{os}}{V_{t}}}\right]\right)Ae^{\frac{V_{os}}{V_{t}}}$$

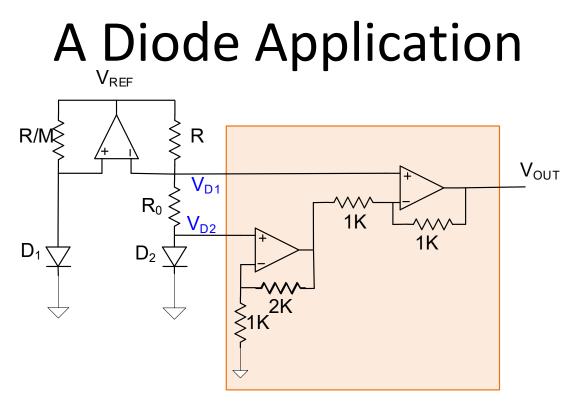
$$I_{D1}(T) = MI_{D2}(T)$$

$$V_{t} = \frac{k}{q}T$$

$$\left(J_{SX}\left[T^{m}e^{\frac{-V_{os}}{V_{t}}}\right]\right)Ae^{\frac{V_{os}}{V_{t}}}$$

$$Cancelling terms and taking ln we obtain
$$V_{D1} - V_{D2} = V_{t} In M$$
Thus
$$V_{OUT} = 2(V_{D1} - V_{D2}) = 2In M \bullet \frac{k}{q} T$$

$$T = V_{OUT} \frac{q}{2k ln M}$$$$



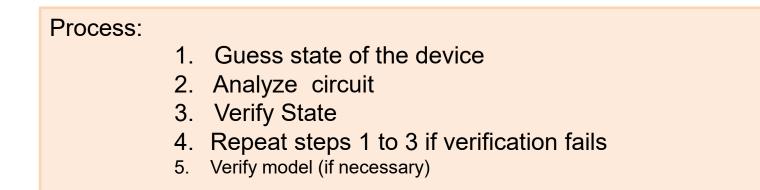
May need compensation and startup circuits

If buffer/amplifier added, serves as temperature sensor at V<sub>OUT</sub>

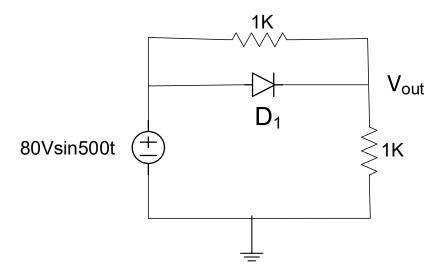
 $V_{OUT} = 2(V_{D1} - V_{D2}) \qquad \qquad T = V_{OUT} \frac{q}{2k \ln M}$ For appropriate R<sub>0</sub>, serves as bandgap voltage reference  $V_{REF} = V_{D1} + \frac{R}{R_0}(V_{D1} - V_{D2}) \qquad \qquad \ref{eq:result}$ 

Analysis of  $V_{REF}$  to show output is nearly independent of T and  $V_{DD}$  is more tedious

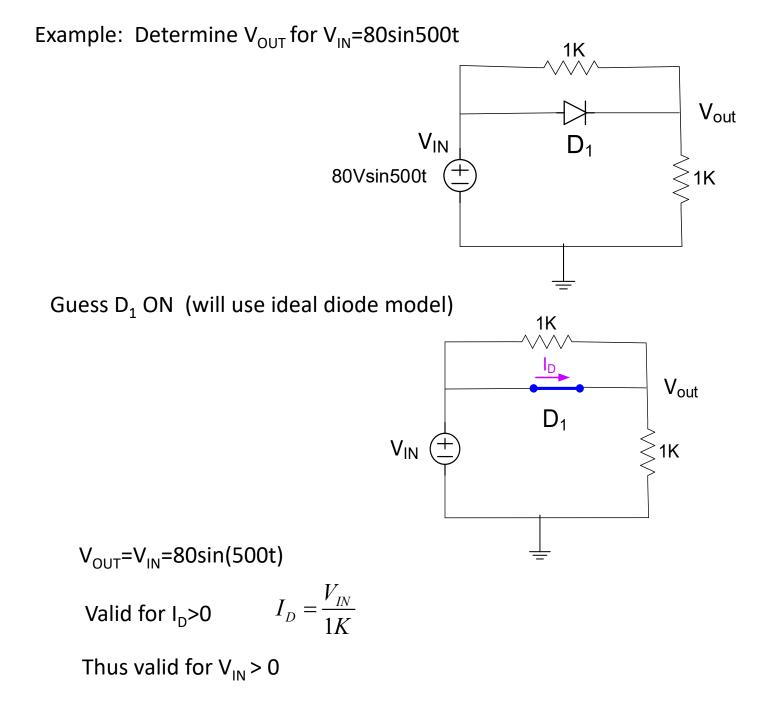
### Use of <u>Piecewise</u> Models for Nonlinear Devices when Analyzing Electronic Circuits

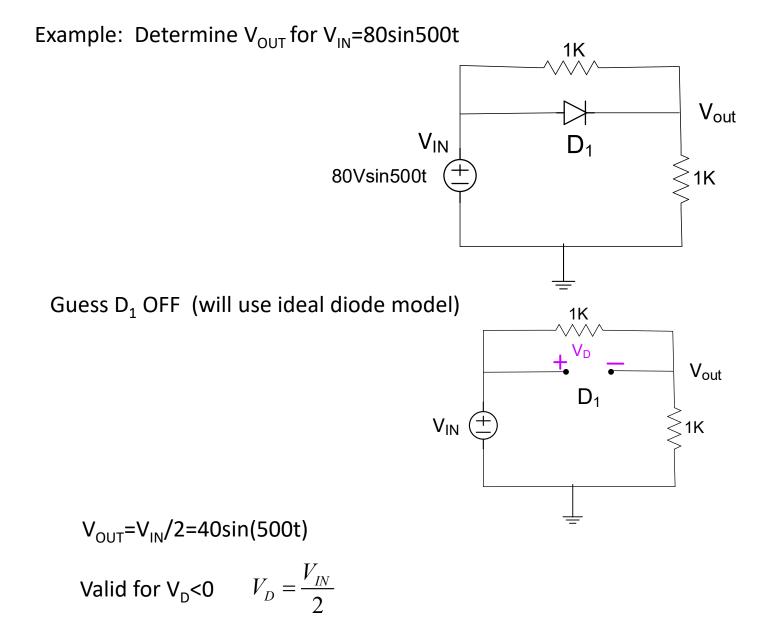


What about nonlinear circuits (using piecewise models) with time-varying inputs?



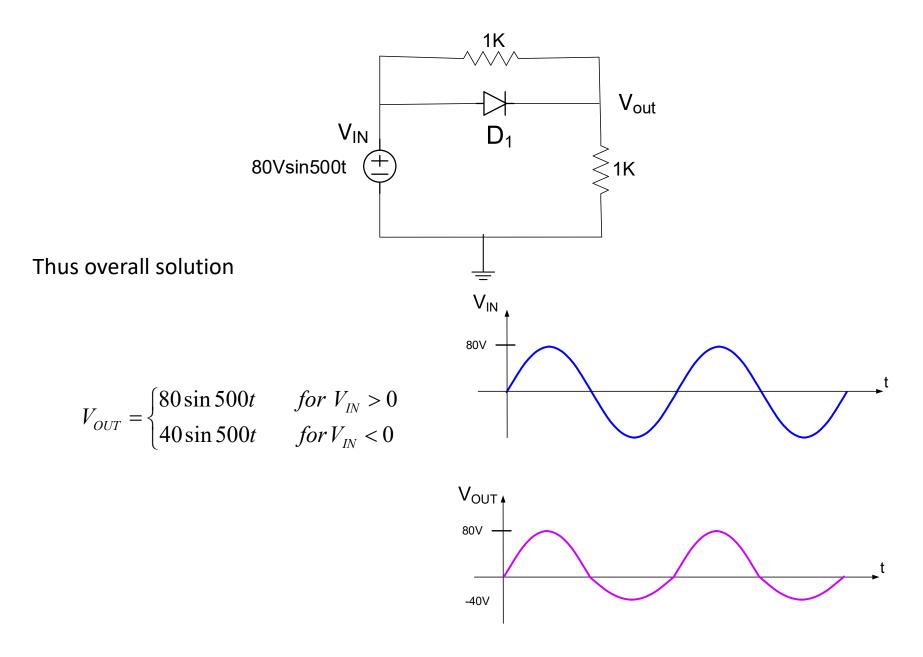
Same process except state verification (step 3) may include a range where solution is valid





Thus valid for  $V_{IN} < 0$ 

Example: Determine  $V_{OUT}$  for  $V_{IN}$ =80sin500t

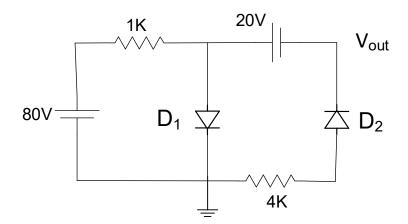


### Use of <u>Piecewise</u> Models for Nonlinear Devices when Analyzing Electronic Circuits

#### Process:

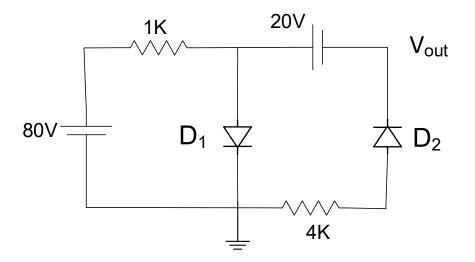
- 1. Guess state of the device
- 2. Analyze circuit
- 3. Verify State
- 4. Repeat steps 1 to 3 if verification fails
- 5. Verify model (if necessary)

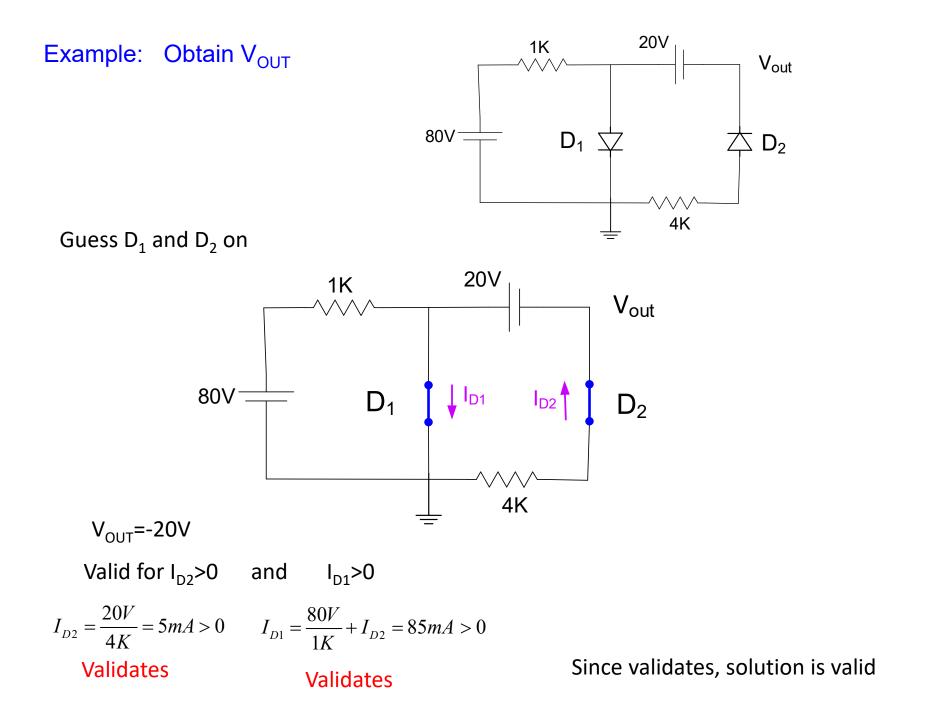
What about circuits (using piecewise models) with multiple nonlinear devices?

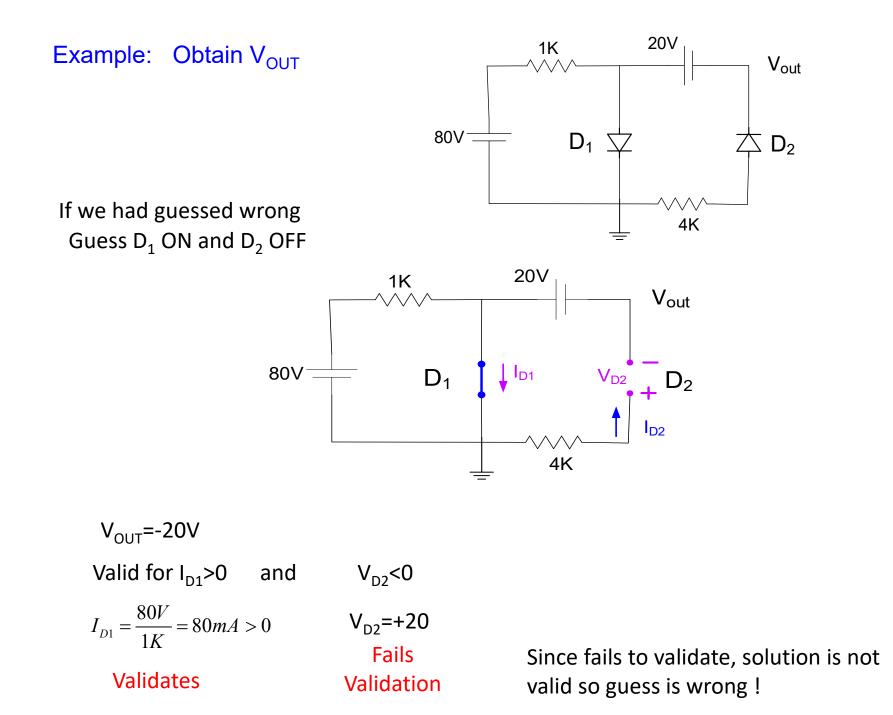


Guess state for each device (multiple combinations possible)

Example: Obtain V<sub>OUT</sub>







### Use of <u>Piecewise</u> Models for Nonlinear Devices when Analyzing Electronic Circuits

#### Single Nonlinear Device

Process:

- 1. Guess state of the device
- 2. Analyze circuit
- 3. Verify State
- 4. Repeat steps 1 to 3 if verification fails
- 5. Verify model (if necessary)

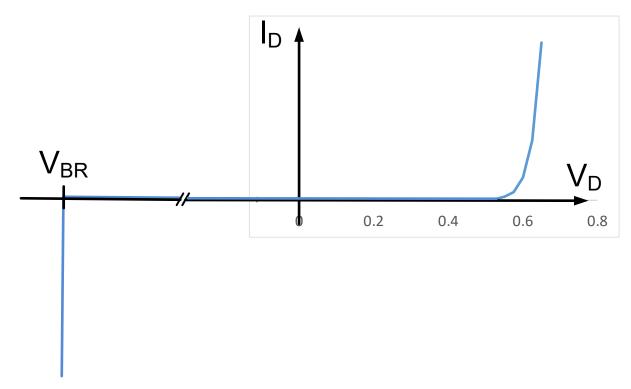
#### Multiple Nonlinear Devices

Process:

- 1. Guess state of each device (may be multiple combinations)
- 2. Analyze circuit
- 3. Verify State
- 4. Repeat steps 1 to 3 if verification fails
- 5. Verify models (if necessary)

Analytical solutions of circuits with multiple nonlinear devices are often impossible to obtain if detailed non-piecewise nonlinear models are used

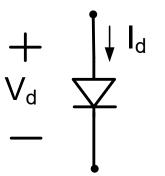
### Diode Breakdown

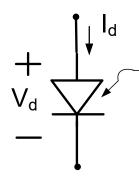


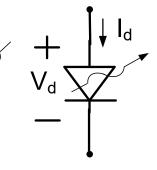
- Diodes will "break down" if a large reverse bias is applied
- Unless current is limited, reverse breakdown is destructive
- Breakdown is very sharp
- For many signal diodes,  $V_{BR}$  is in the -100V to -1000V range
- Relatively easy to design circuits so that with correct diodes, breakdown will not occur
- Zener diodes have a relatively small breakdown and current is intentionally limited to use this breakdown to build voltage references

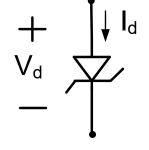
### **Types of Diodes**

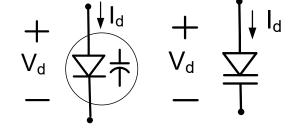
#### pn junction diodes











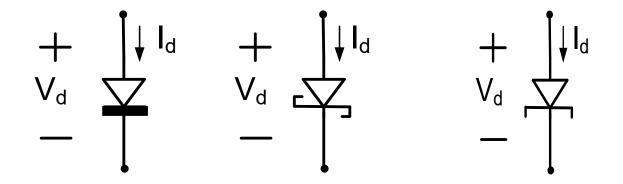
Signal or Rectifier

Pin or Photo Light Emitting LED Laser Diode

Zener

Varactor or Varicap

**Metal-semiconductor junction diodes** 



Schottky Barrier

# **Basic Devices and Device Models**

- Resistor
- Diode

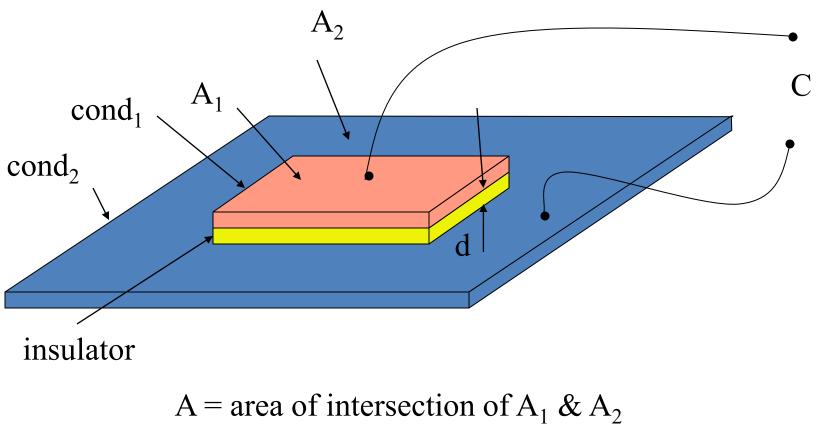


- MOSFET
- BJT

# Capacitors

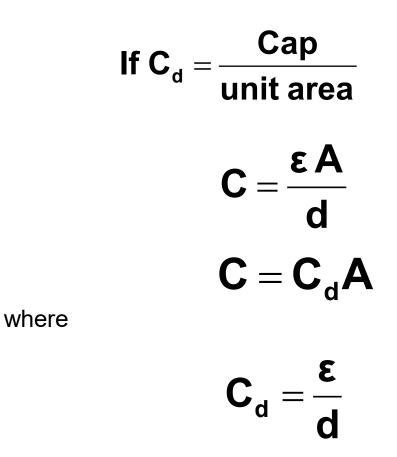
- Types
  - Parallel Plate
  - Fringe
  - Junction

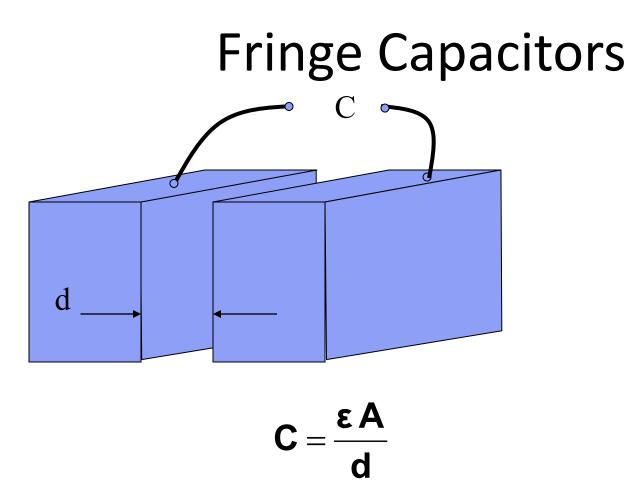
# **Parallel Plate Capacitors**



One (top) plate intentionally sized smaller to determine C  $C = \frac{\in A}{d}$ 

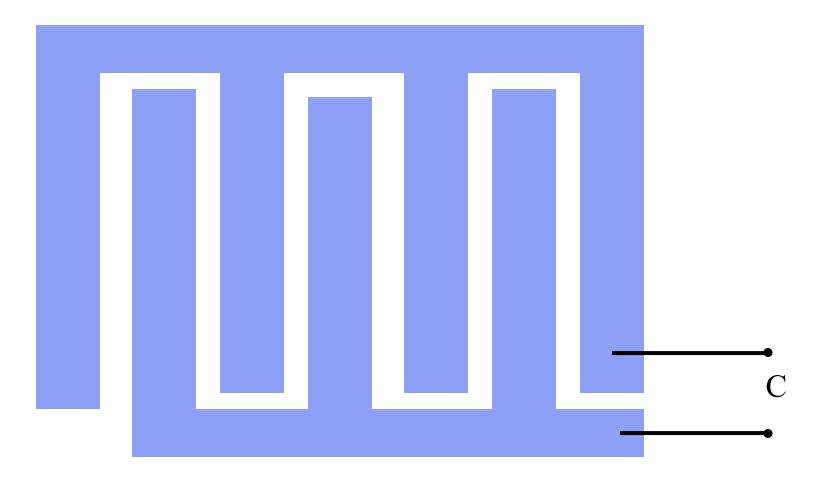
### **Parallel Plate Capacitors**



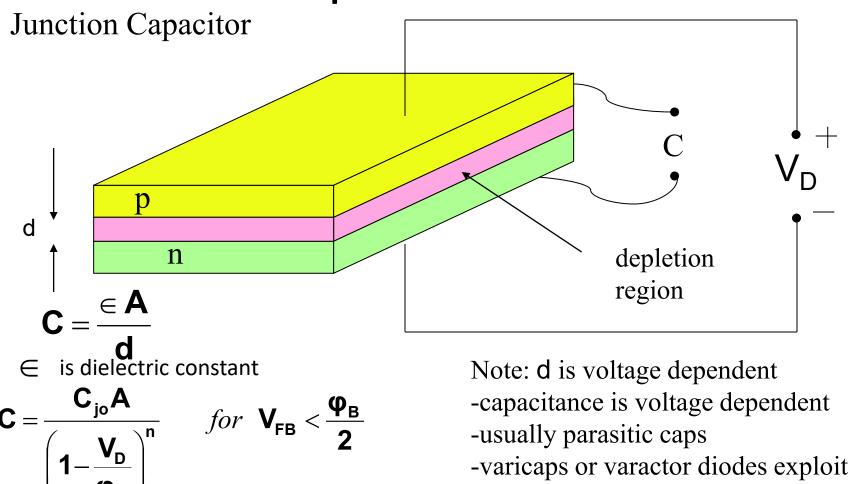


A is the area where the two plates are parallel Only a single layer is needed to make fringe capacitors

# **Fringe Capacitors**



### Capacitance

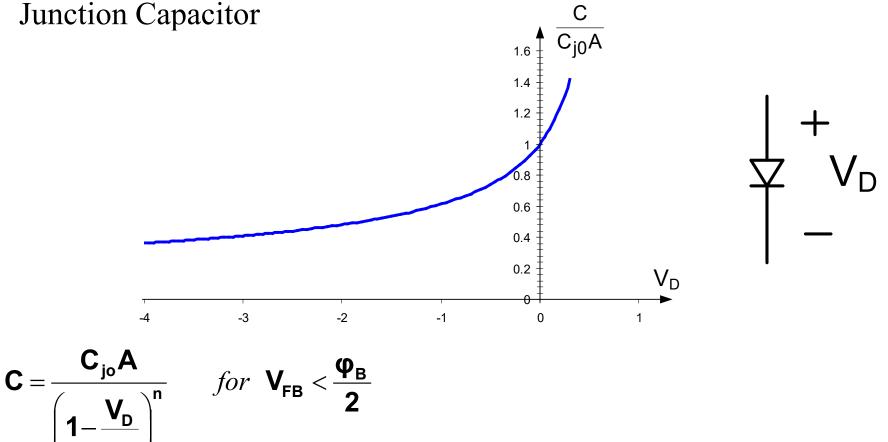


 $C_{j0}$  is the zero—bias junction capacitance density Model parameters { $C_{j0}$ , n,  $\phi_B$ } Design parameters {A}

 $\phi_{\scriptscriptstyle B}\cong 0.6V \qquad n\simeq 0.5 \qquad {\sf C}_{_{jo}} \text{ highly process dependent around 500aF/} \mu\text{m}^2$ 

voltage dep. of C

# Capacitance



Voltage dependence is substantial

 $\phi_{\scriptscriptstyle B}\,{\simeq}\,0.6V\quad n\,{\simeq}\,0.5$ 

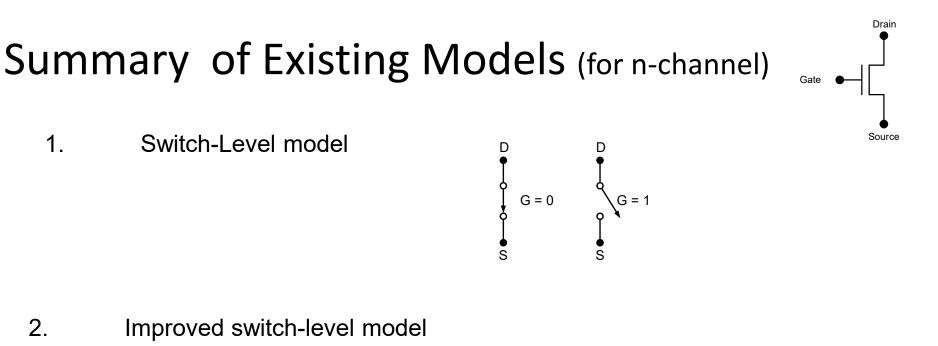
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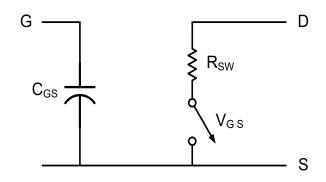
# **Basic Devices and Device Models**

- Resistor
- Diode
- Capacitor



• BJT



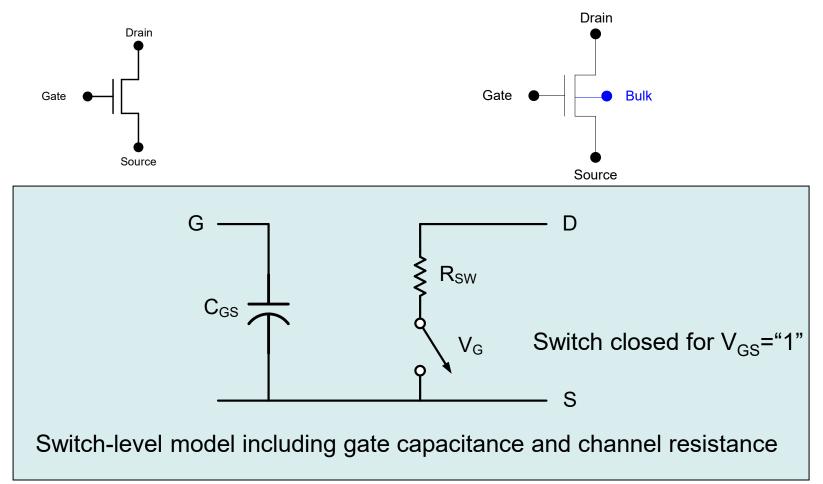


1.

2.

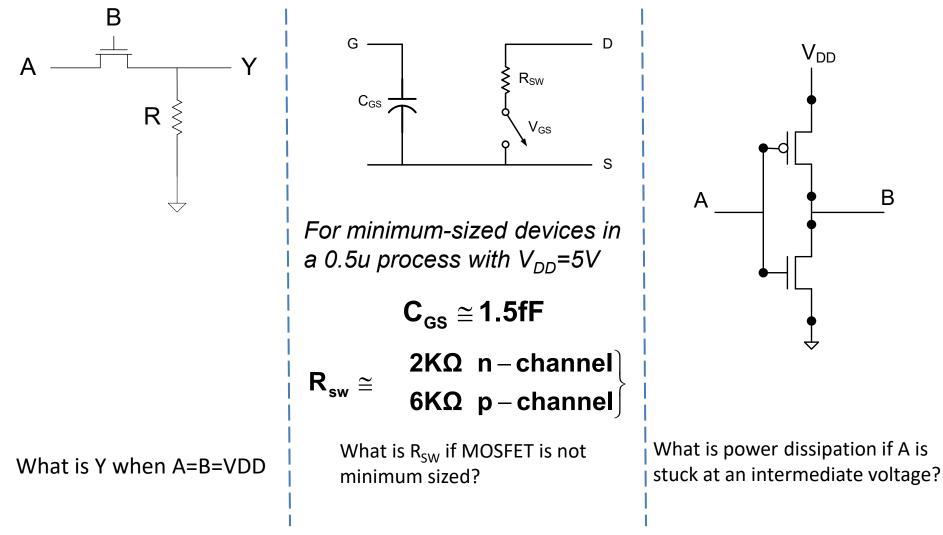
Switch closed for  $|V_{GS}|$  = large Switch open for  $|V_{GS}|$  = small

# Improved Switch-Level Model



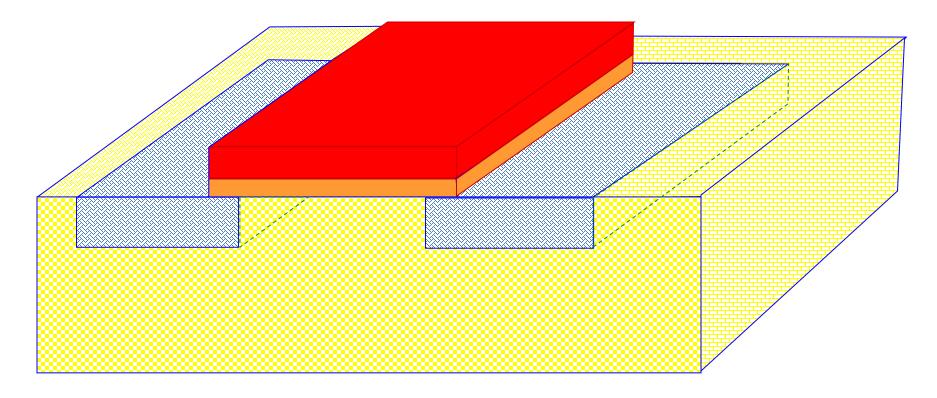
- Connect the gate capacitance to the source to create lumped model
- Still neglect bulk connection

### Limitations of Existing MOSFET Models



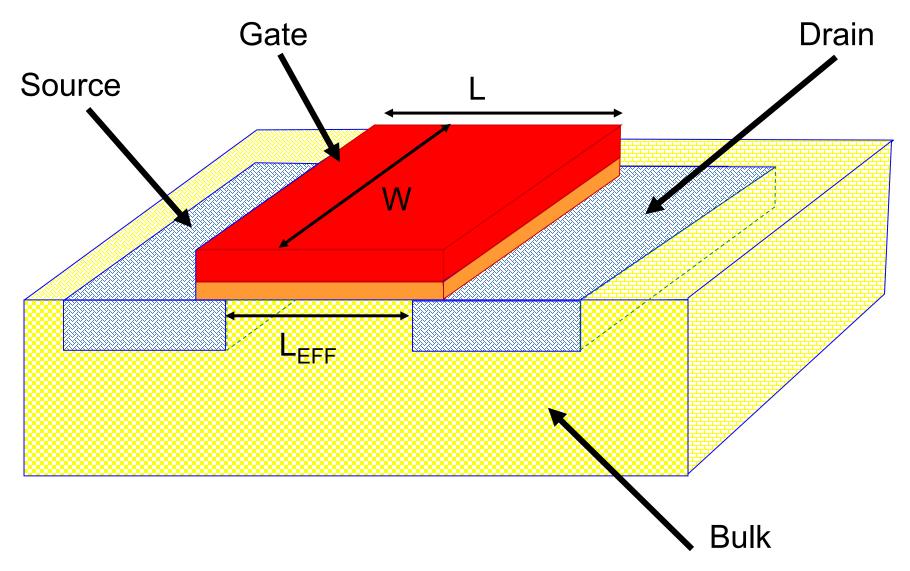
### Better Model of MOSFET is Needed!

# n-Channel MOSFET

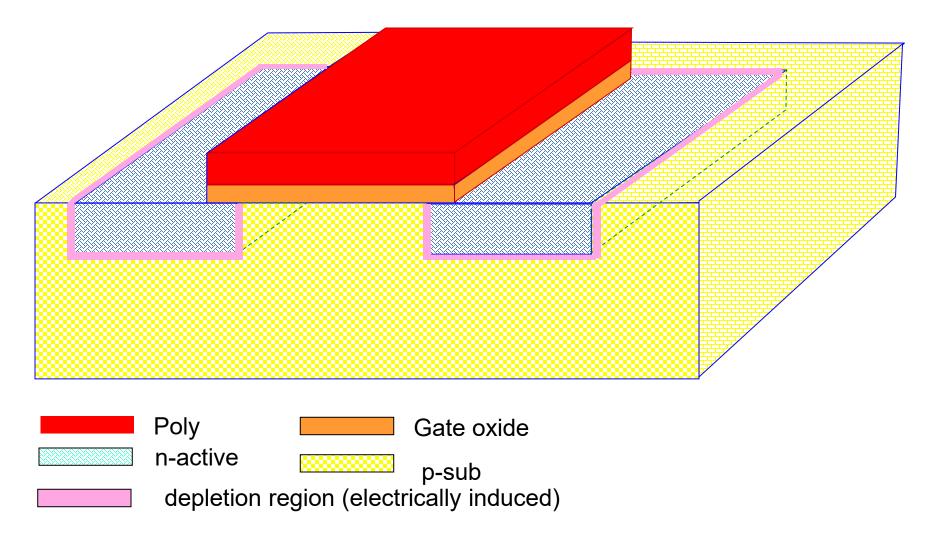




# n-Channel MOSFET

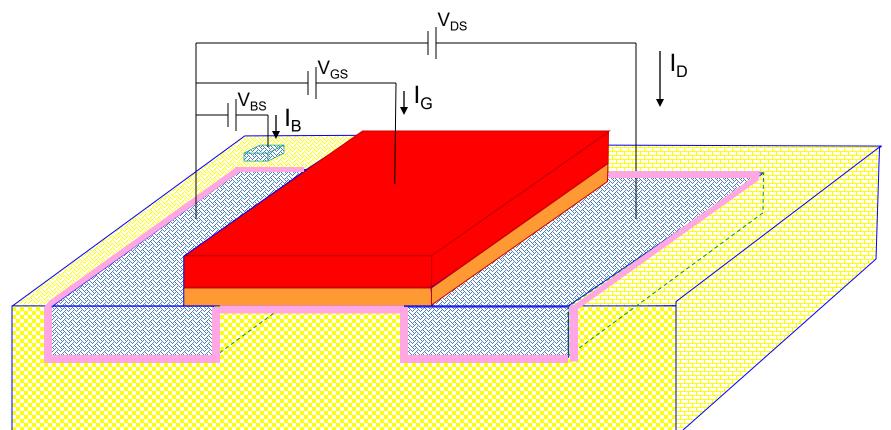


# n-Channel MOSFET



- In what follows assume all pn junctions reverse biased (almost always used this way)
- Extremely small reverse bias pn junction current can be neglected in most applications

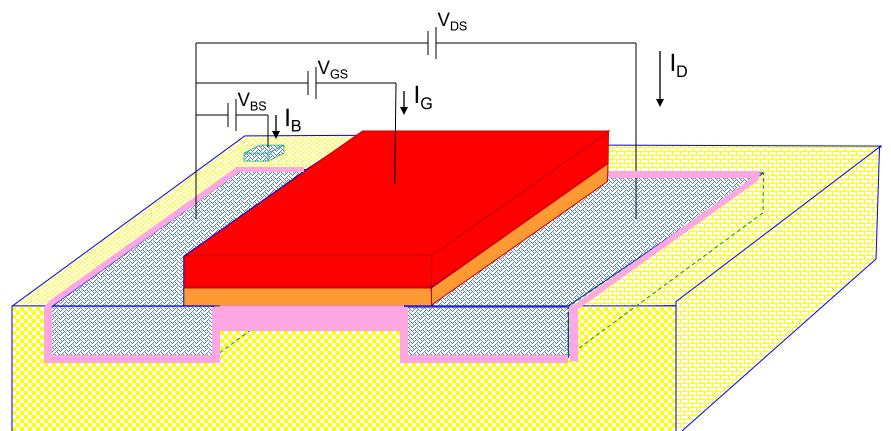
### n-Channel MOSFET Operation and Model



Apply small  $V_{GS}$ ( $V_{DS}$  and  $V_{BS}$  assumed to be small) Depletion region electrically induced in channel Termed "cutoff" region of operation

I<sub>D</sub>=0 I<sub>G</sub>=0 I<sub>B</sub>=0

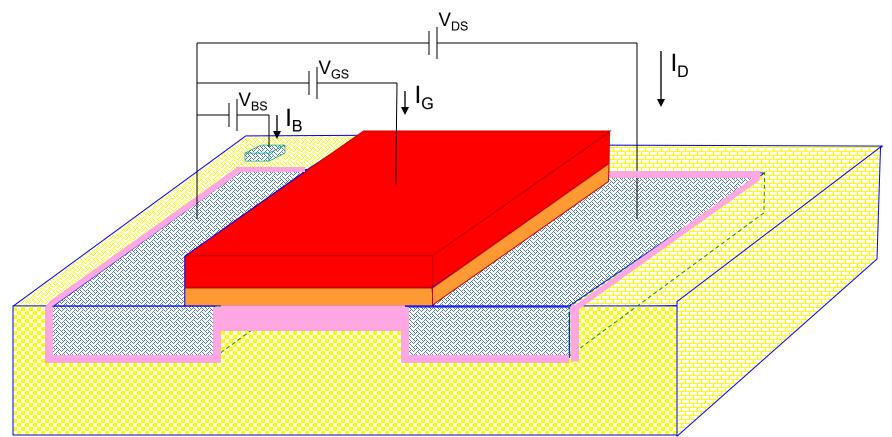
### n-Channel MOSFET Operation and Model

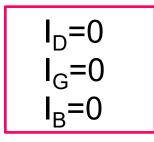


Increase  $V_{GS}$ ( $V_{DS}$  and  $V_{BS}$  assumed to be small)

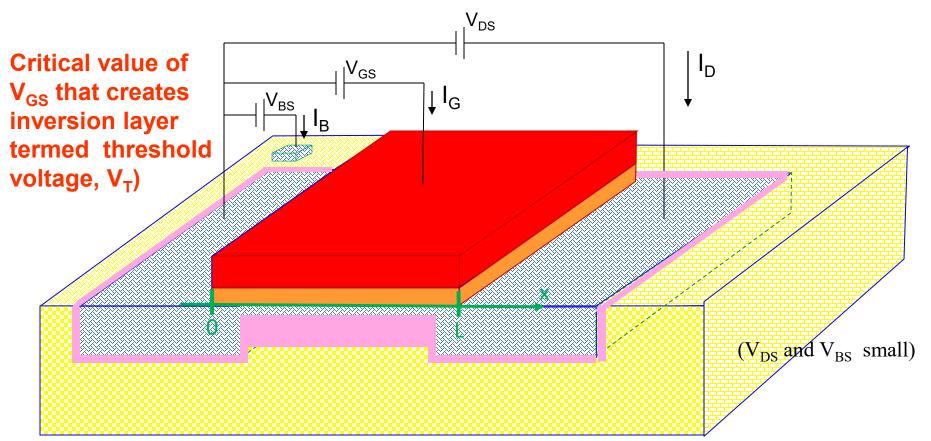
Depletion region in channel becomes larger

I<sub>D</sub>=0 I<sub>G</sub>=0 I<sub>B</sub>=0





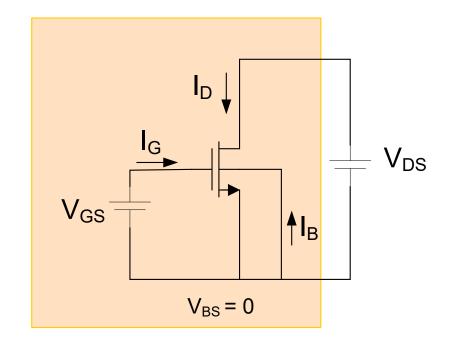
Model in Cutoff Region

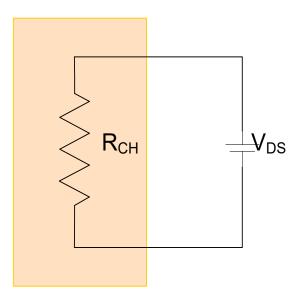


Increase V<sub>GS</sub> more

Inversion layer forms in channel Inversion layer will support current flow from D to S Channel behaves as thin-film resistor  $I_D R_{CH} = V_{DS}$  $I_G = 0$  $I_B = 0$ 

# **Triode Region of Operation**





For V<sub>DS</sub> small  

$$R_{CH} = \frac{L}{W} \frac{1}{(V_{GS} - V_{TH}) \mu C_{OX}}$$

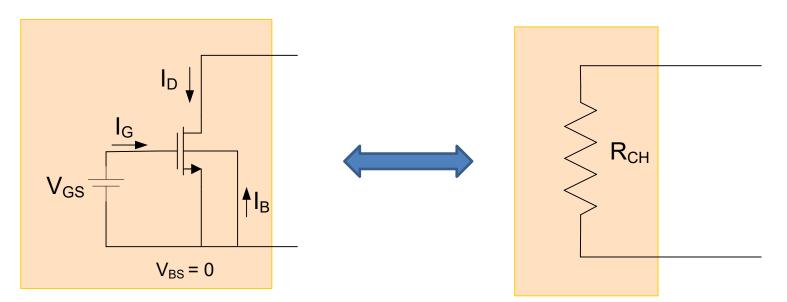
$$I_{D} = \mu C_{OX} \frac{W}{L} (V_{GS} - V_{TH}) V_{DS}$$

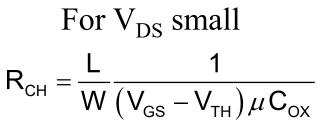
$$I_{G} = I_{B} = 0$$

Behaves as a resistor between drain and source

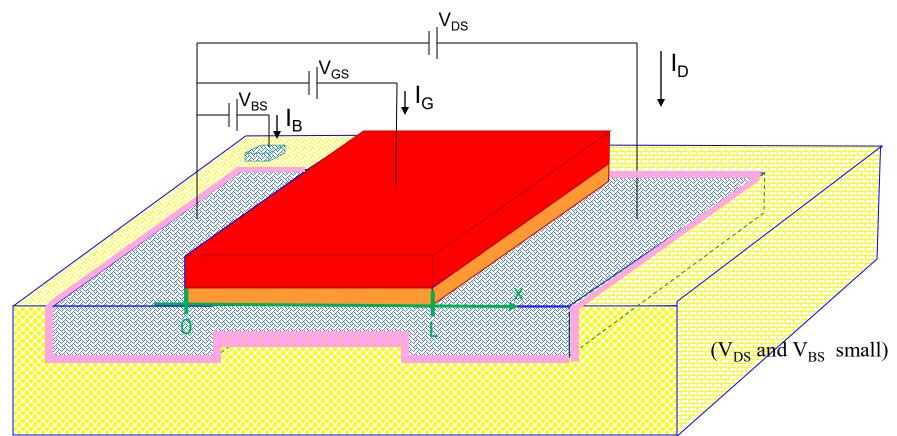
Model in Deep Triode Region

# Triode Region of Operation





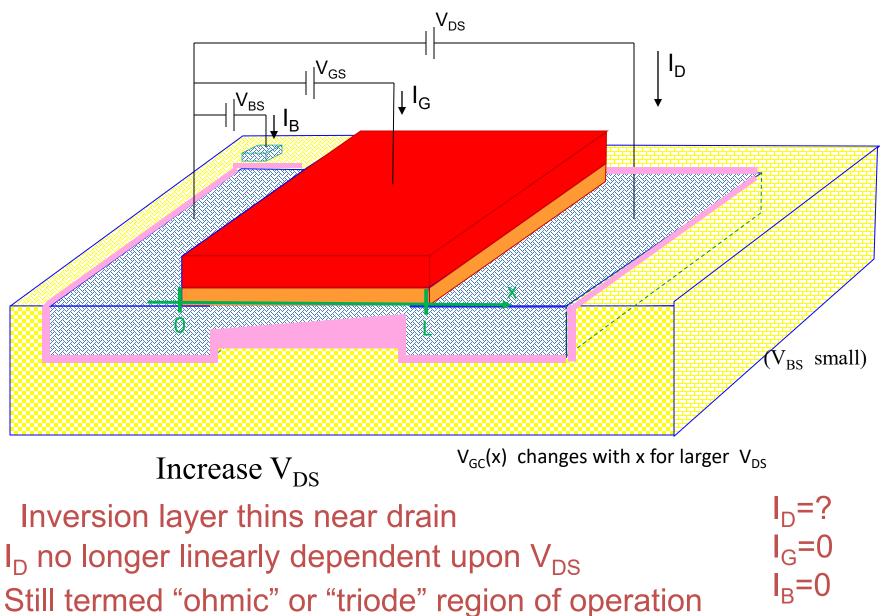
Resistor is controlled by the voltage  $V_{GS}$ Termed a "Voltage Controlled Resistor" (VCR)



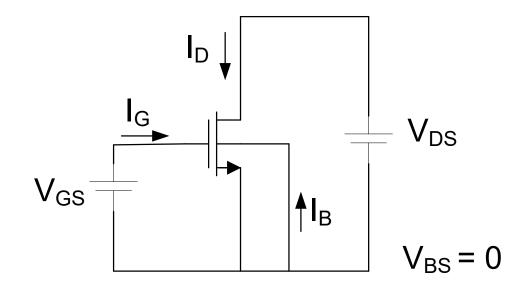
 $V_{GC}(x)$  approx. constant for small  $V_{DS}$ 

Increase  $V_{GS}$  more Inversion layer in channel thickens  $R_{CH}$  will decrease Termed "ohmic" or "triode" region of operation

 $I_D R_{CH} = V_{DS}$  $I_G = 0$  $I_B = 0$ 



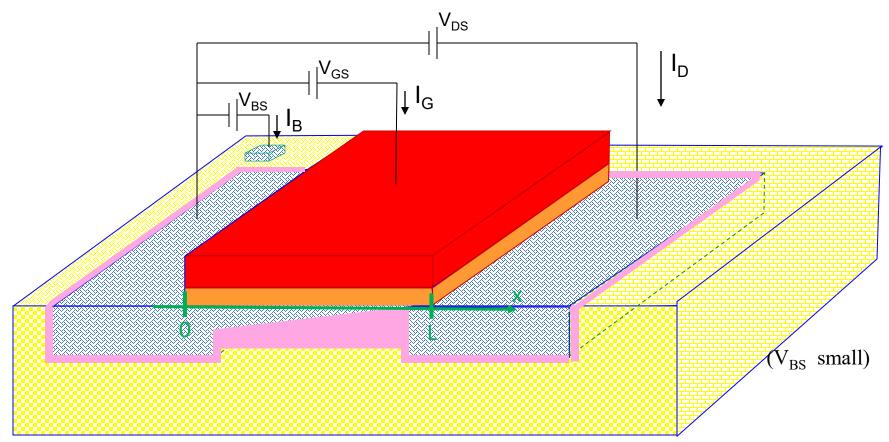
# Triode Region of Operation



For V<sub>DS</sub> larger  $R_{CH} = \frac{L}{W} \frac{1}{(V_{GS} - V_{TH}) \mu C_{OX}}$ 

$$I_{D} = \mu C_{OX} \frac{W}{L} \left( V_{GS} - V_{TH} - \frac{V_{DS}}{2} \right) V_{DS}$$
$$I_{G} = I_{B} = 0$$

#### Model in Triode Region



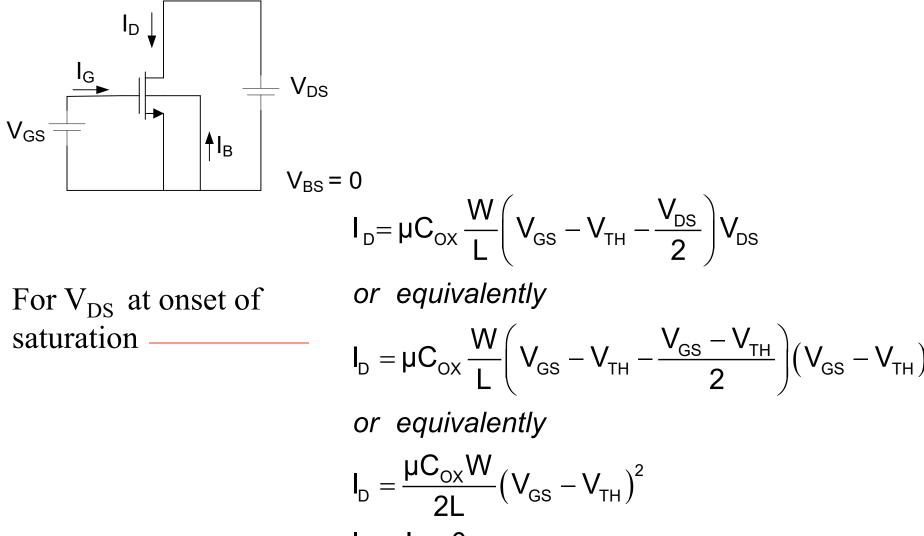
Increase  $V_{DS}$  even more

 $V_{GC}(L) = V_{TH}$  when channel saturates

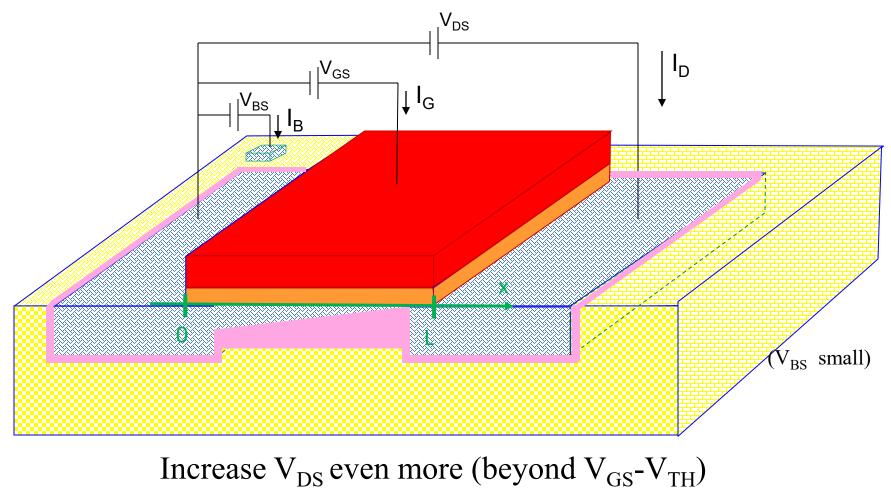
I<sub>D</sub>=? I<sub>G</sub>=0 I<sub>B</sub>=0

Inversion layer disappears near drain Termed "saturation" region of operation Saturation first occurs when  $V_{DS}=V_{GS}-V_{TH}$ 

# Saturation Region of Operation



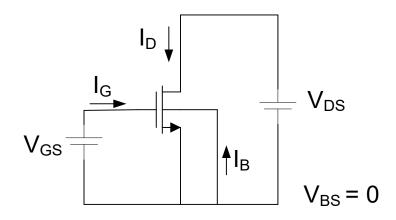
 $I_{\rm G} = I_{\rm B} = 0$ 



I<sub>D</sub>=? I<sub>G</sub>=0 I<sub>B</sub>=0

Nothing much changes !! Termed "saturation" region of operation

# Saturation Region of Operation



#### For $V_{DS}$ in Saturation

$$I_{D} = \frac{\mu C_{OX} W}{2L} (V_{GS} - V_{TH})^{2}$$
$$I_{G} = I_{B} = 0$$

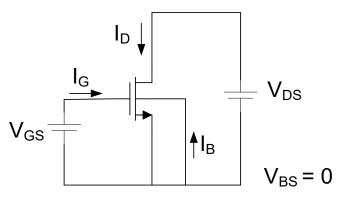
Model in Saturation Region

# **Model Summary**

#### n-channel MOSFET

Notation change:  $V_T = V_{TH}$ , don't confuse  $V_T$  with  $V_t = kT/q$ 

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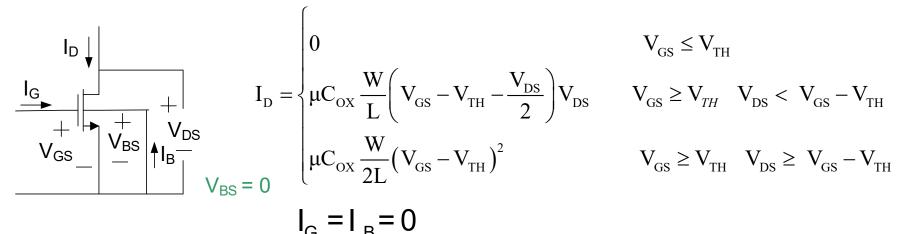
$$I_{D} = \begin{cases} 0 & V_{GS} \leq V_{TH} & \text{Cutoff} \\ \mu C_{OX} \frac{W}{L} \left( V_{GS} - V_{TH} - \frac{V_{DS}}{2} \right) V_{DS} & V_{GS} \geq V_{TH} & V_{DS} < V_{GS} - V_{TH} & \text{Triode} \\ \mu C_{OX} \frac{W}{2L} \left( V_{GS} - V_{TH} \right)^{2} & V_{GS} \geq V_{TH} & V_{DS} \geq V_{GS} - V_{TH} & \text{Saturation} \\ I_{G} = I_{B} = 0 \end{cases}$$

Model Parameters: {μ, V<sub>TH</sub>, C<sub>OX</sub>} Design Parameters : {W, L} This is a piecewise model (not piecewise linear though) Piecewise model is continuous at transition between regions

(Deep triode special case of triode where  $V_{DS}$  is small  $R_{CH} = \frac{L}{W} \frac{1}{(V_{GS} - V_{TH}) \mu C_{OX}}$ ) Note: This is the third model we have introduced for the MOSFET

# **Model Summary**

n-channel MOSFET

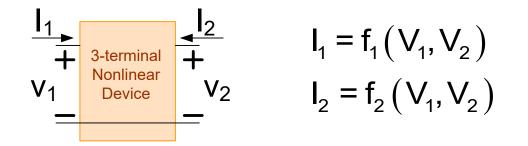


**Observations about this model** (developed for V<sub>BS</sub>=0):

 $I_{D} = f_{1} (V_{GS}, V_{DS})$  $I_{G} = f_{2} (V_{GS}, V_{DS})$  $I_{B} = f_{3} (V_{GS}, V_{DS})$ 

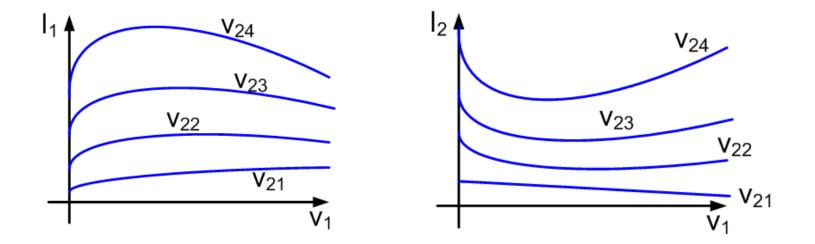
This is a nonlinear model characterized by the functions  $f_1$ ,  $f_2$ , and  $f_3$  where we have assumed that the port voltages  $V_{GS}$  and  $V_{DS}$  are the independent variables and the drain currents are the dependent variables

## **General Nonlinear Models**

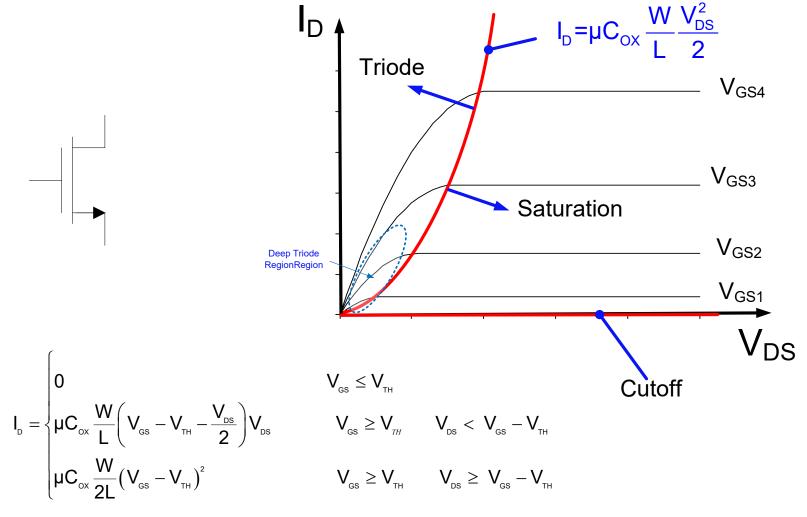


 $I_1$  and  $I_2$  are 3-dimensional relationships which are often difficult to visualize

Two-dimensional representation of 3-dimensional relationships



## **Graphical Representation of MOS Model**



 $I_{G} = I_{B} = 0$ 

Parabola separated triode and saturation regions and corresponds to  $V_{DS}=V_{GS}-V_{TH}$ 



# Stay Safe and Stay Healthy !

## End of Lecture 16